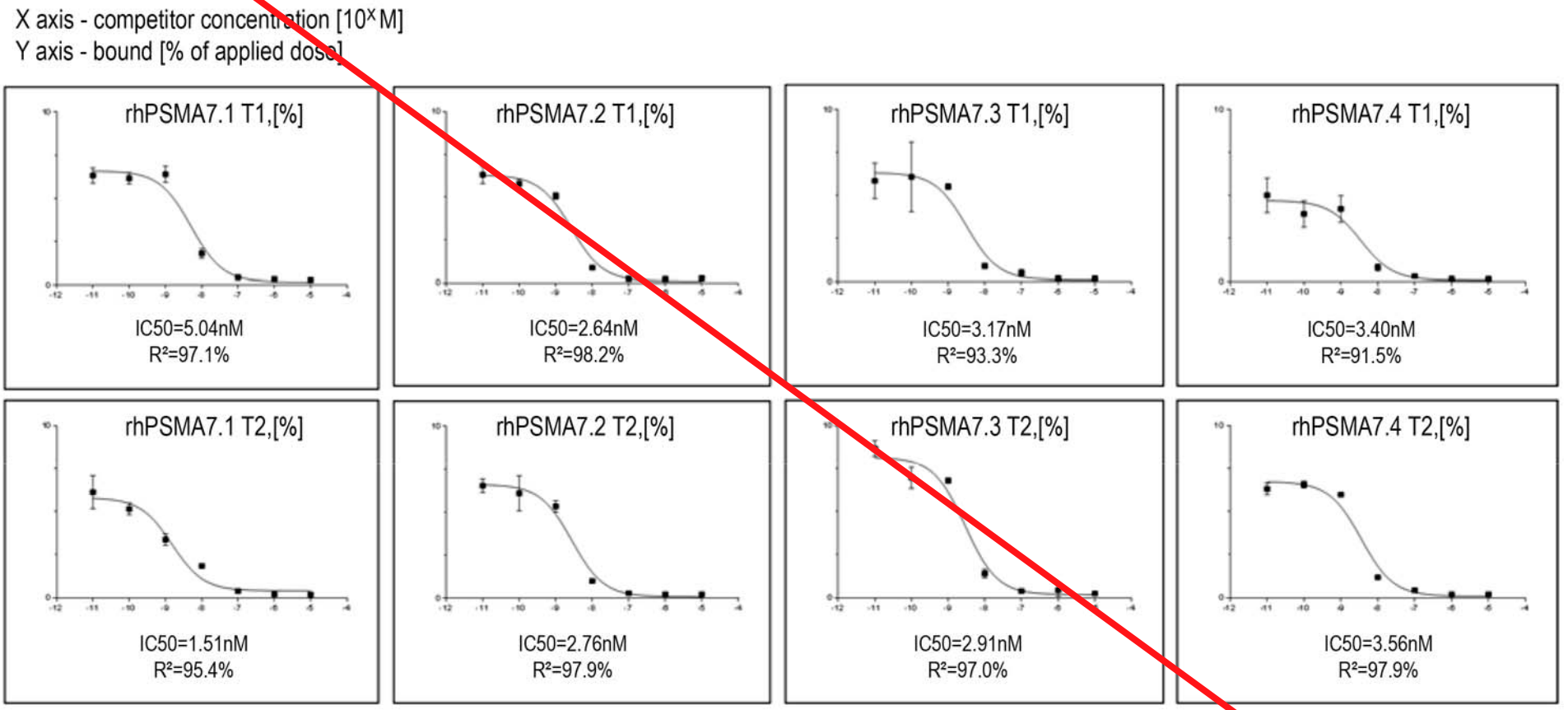

X axis - competitor concentration [10^X M]
Y axis - bound [% of applied dose]
rhPSMA7.1 T1,[%]
IC50=5.04nM
R²=97.1%
rhPSMA7.2 T1,[%]
IC50=2.64nM
R²=98.2%
rhPSMA7.3 T1,[%]
IC50=3.17nM
R²=93.3%
rhPSMA7.4 T1,[%]
IC50=3.40nM
R²=91.5%
rhPSMA7.1 T2,[%]
IC50=1.51nM
R²=95.4%
rhPSMA7.2 T2,[%]
IC50=2.76nM
R²=97.9%
rhPSMA7.3 T2,[%]
IC50=2.91nM
R²=97.0%
rhPSMA7.4 T2,[%]
IC50=3.56nM
R²=97.9%

Fig. 6b

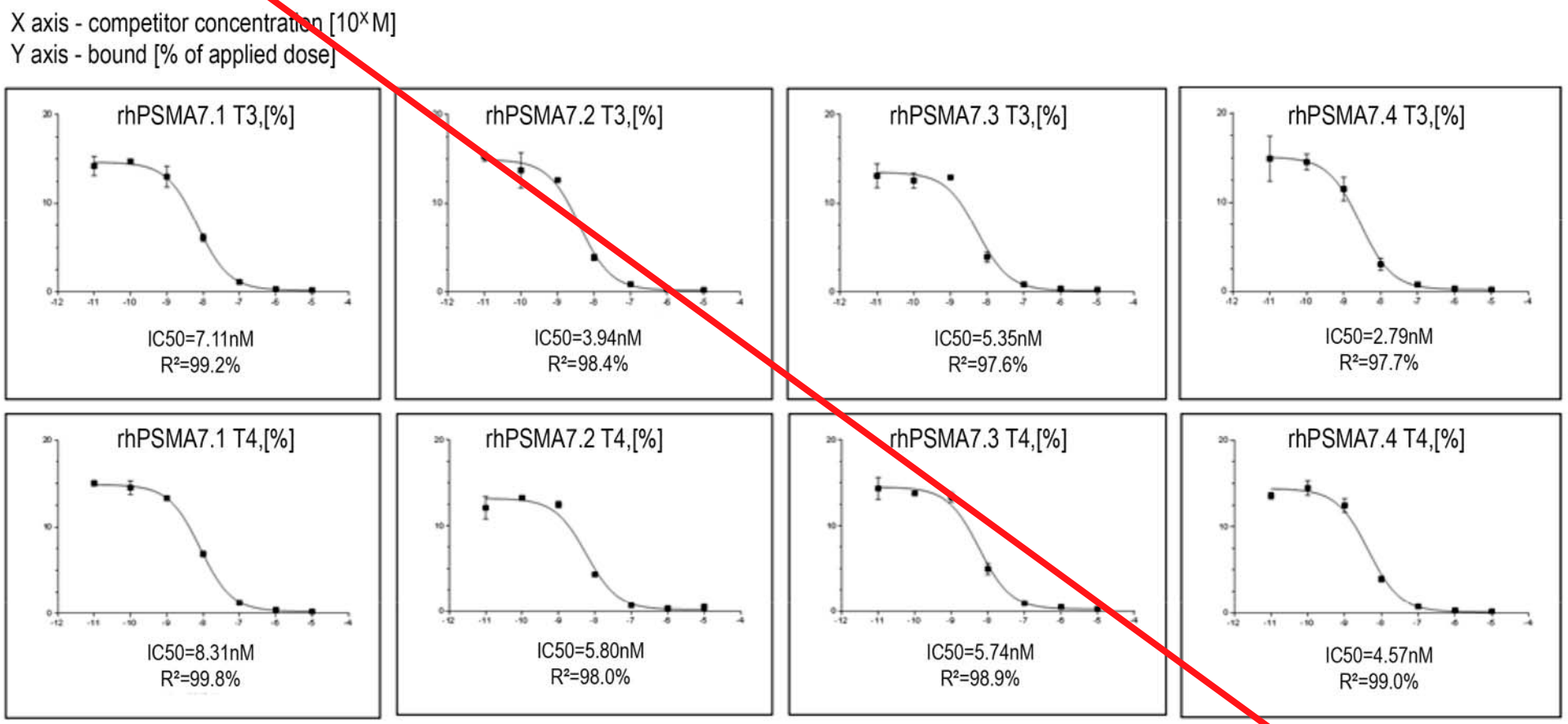


Fig. 6b (continued)

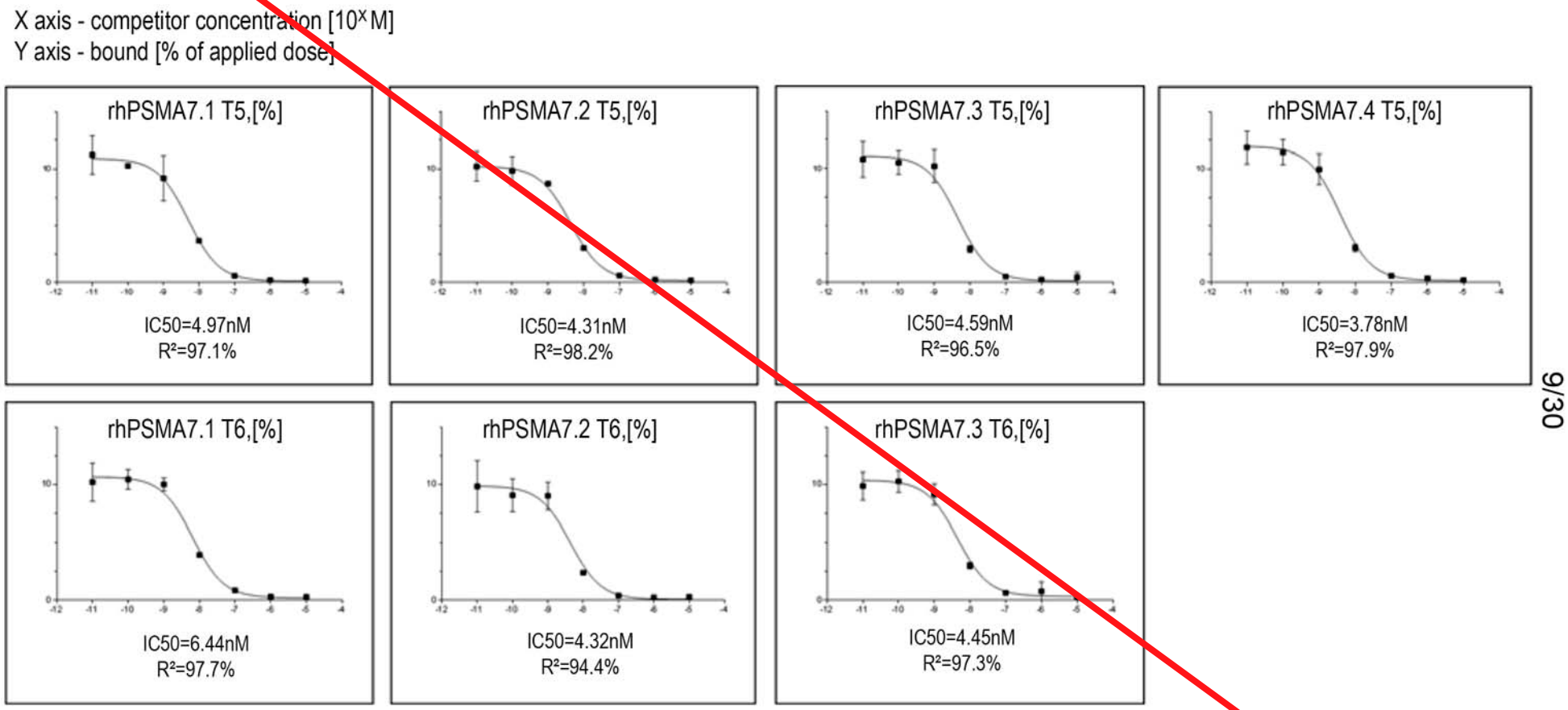


Fig. 6b (continued)

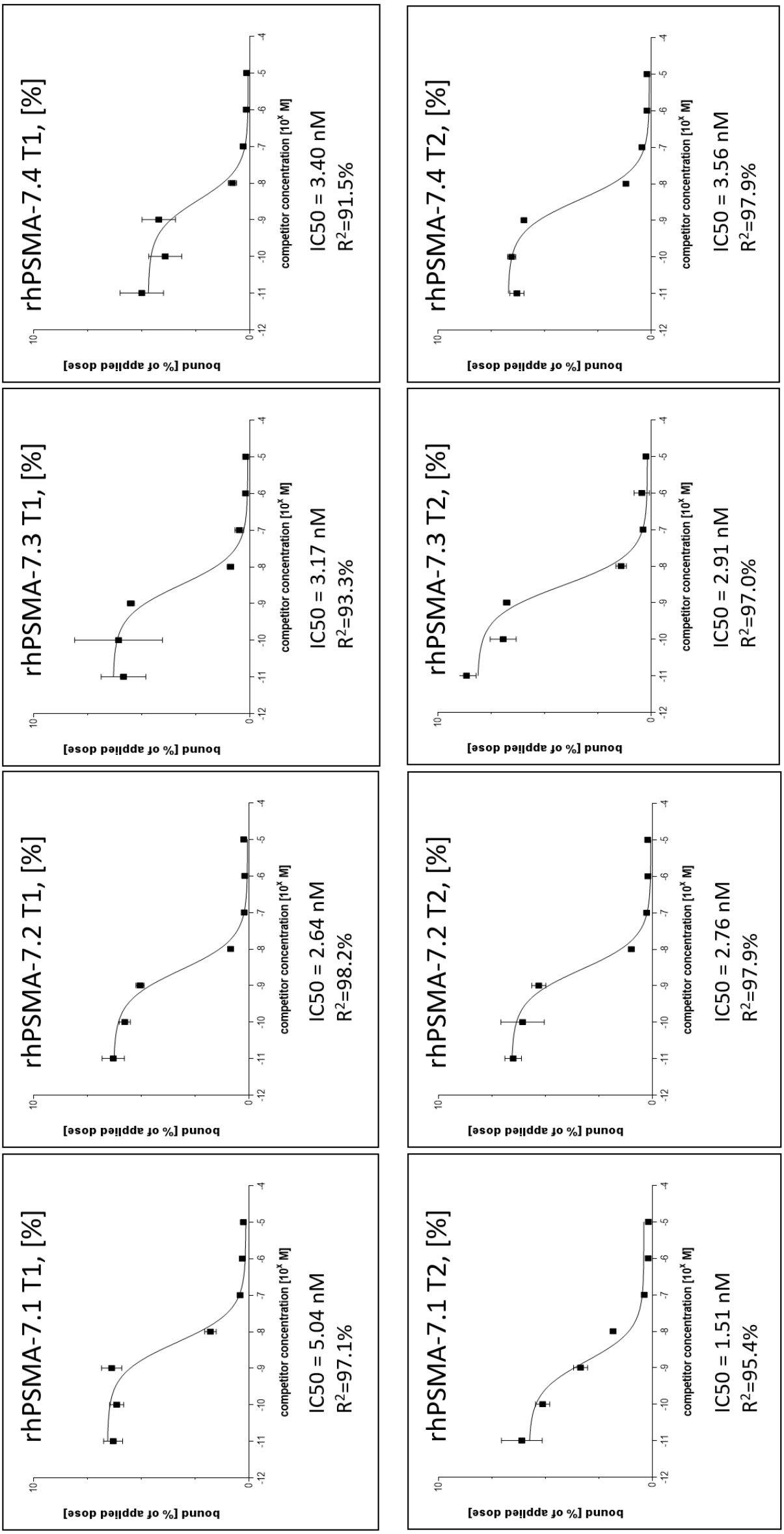

rhPSMA-7.1 T1, [%]
IC50 = 5.04 nM
R²=97.1%
rhPSMA-7.2 T1, [%]
IC50 = 2.64 nM
R²=98.2%
rhPSMA-7.3 T1, [%]
IC50 = 3.17 nM
R²=93.3%
rhPSMA-7.4 T1, [%]
IC50 = 3.40 nM
R²=91.5%
rhPSMA-7.1 T2, [%]
IC50 = 1.51 nM
R²=95.4%
rhPSMA-7.2 T2, [%]
IC50 = 2.76 nM
R²=97.9%
rhPSMA-7.3 T2, [%]
IC50 = 2.91 nM
R²=97.0%
rhPSMA-7.4 T2, [%]
IC50 = 3.56 nM
R²=97.9%
bound [% of applied dose]
competitor concentration [10^x M]

Fig. 6b

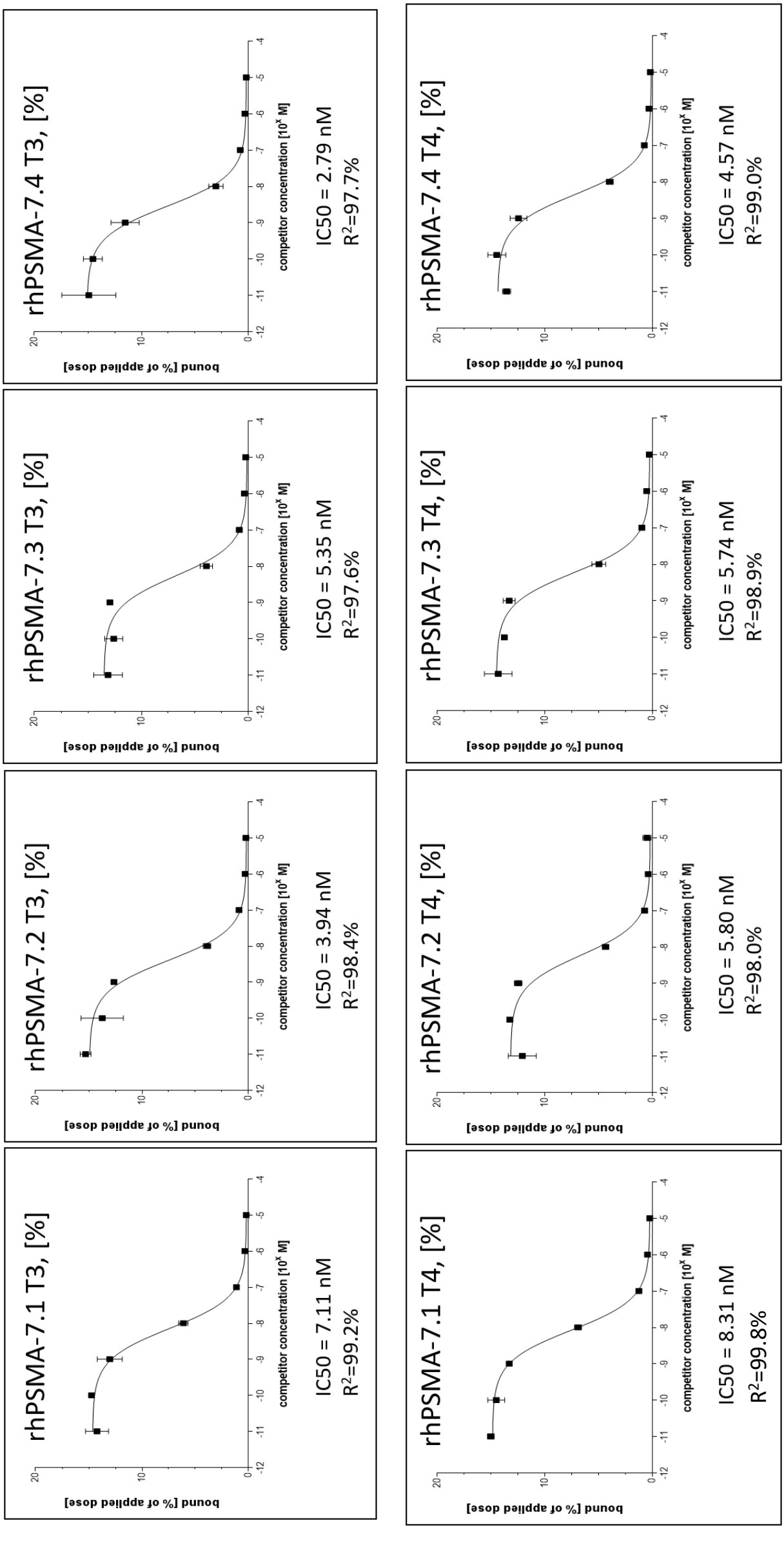
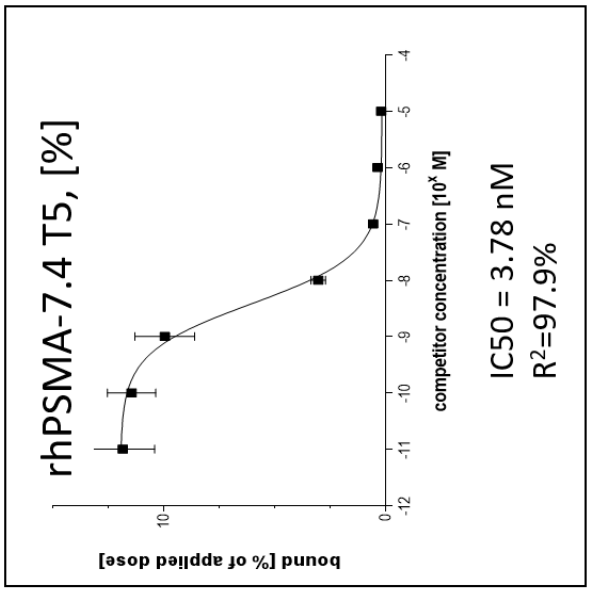
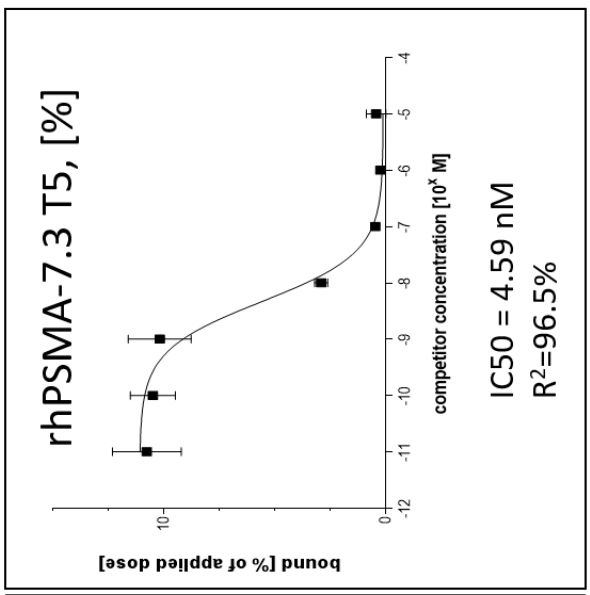
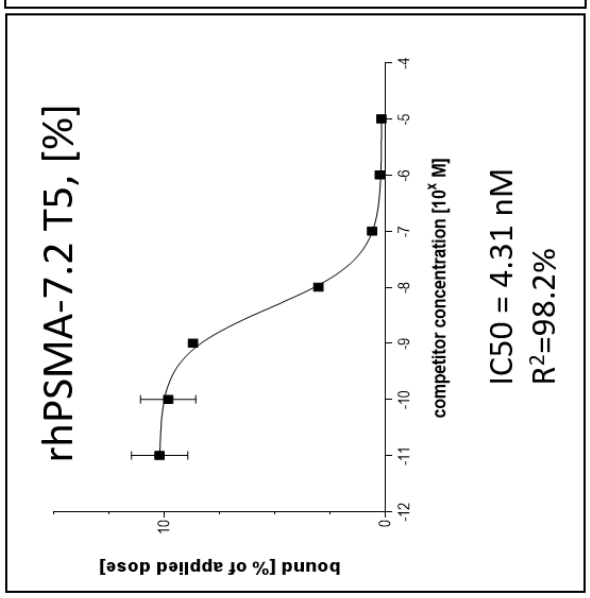
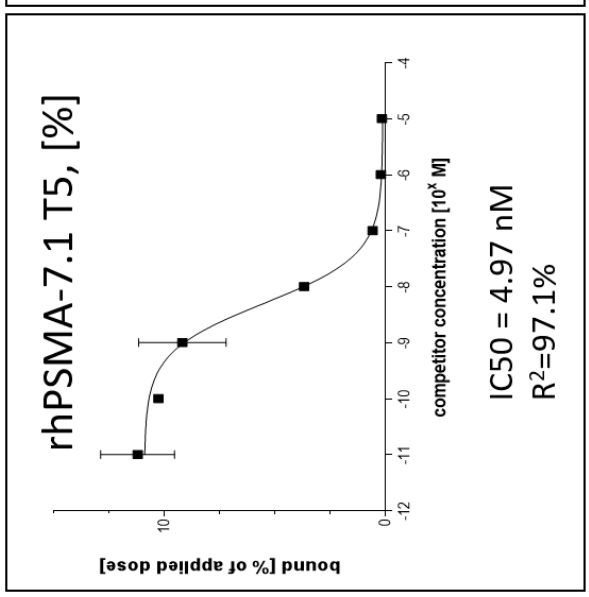


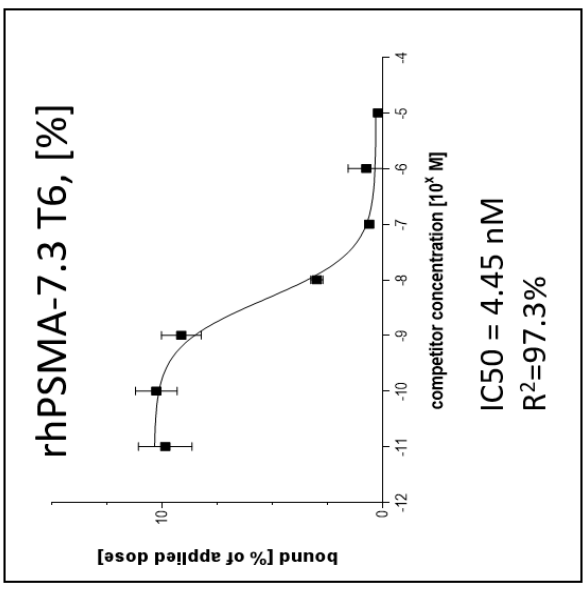
Fig. 6b (continued)

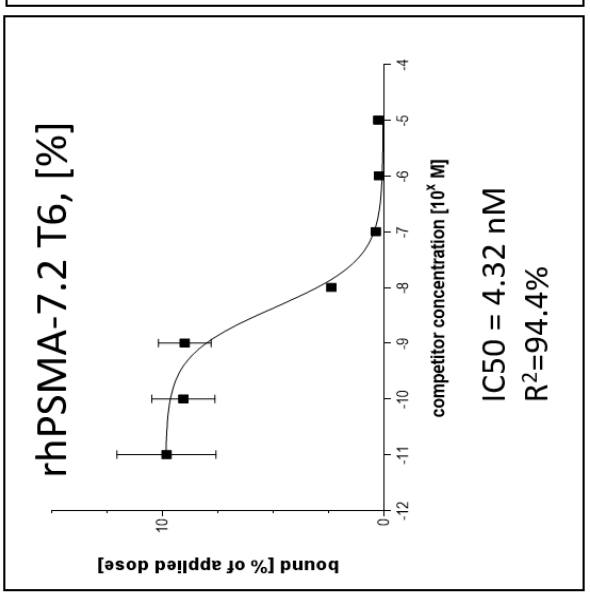












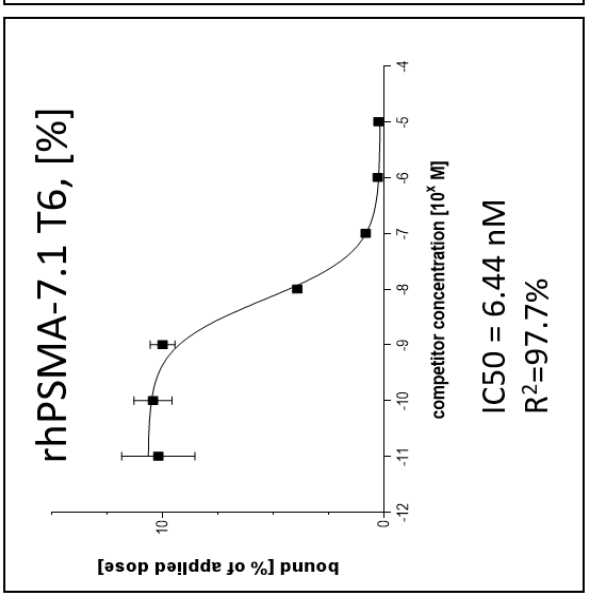


Fig. 6b (continued)